



Serial No. 09/986,445  
SEC.848

UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent application of :  
Young-Rae Park et al. : Group Art Unit 2829  
Serial No. 09/986,445 : Examiner Scott B Geyer  
Filed November 8, 2001 :  
METHOD FOR FABRICATING A CONTACT PAD OF SEMICONDUCTOR DEVICE

#96/Election  
Marsha  
2/26/03

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## RESPONSE

Honorable Commissioner For Patents  
Washington, D.C. 20231

Sir:

In response to the Office Action dated December 18, 2002<sup>1</sup>, Applicant's make the following elections:

- A. 1. chemical mechanical polishing
- B. 1. chemical mechanical polishing
- C. 1. nitride layer
- D. 1. HDP oxide layer
- E. 1. organic anti-reflective layer
- F. 1. doped polysilicon
- G. 1. ceria base CMP slurry
- H. 2. silica base CMP slurry

Claims 1-14 and 16-20 read on the elected species. Claim 1 is generic to all the species.

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<sup>1</sup> The due date has been extended by a concurrently filed Petition For Extension Of Time. Also, it is noted that the U.S. Patent & Trademark Office was officially closed on February 18, 2003, as the result of a snow storm.

Respectfully submitted,

YOUNG-RAE PARK ET AL.

By:

  
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